

Title (en)
DEVICE FOR DEPOSITING THIN LAYERS ON A SUBSTRATE

Title (de)
VORRICHTUNG ZUM ABSCHIEDEN VON D N NEN SCHICHTEN AUF EINEM SU BSTRAT

Title (fr)
DISPOSITIF DE DEPOT DE FINES COUCHES SUR UN SUBSTRAT

Publication
EP 1485518 A1 20041215 (DE)

Application
EP 03708229 A 20030313

Priority
• DE 10211442 A 20020315
• EP 0302608 W 20030313

Abstract (en)
[origin: WO03078681A1] The invention relates to a device for depositing thin layers on a substrate, comprising a process chamber (6) arranged in a reactor housing (1), the bottom of said process chamber being formed by a susceptor (7) for receiving at least one substrate and a gas inlet organ (2) being assigned to the lid of said process chamber, wherein the process gas can be introduced into the process chamber by means of a gas outlet surface which is substantially evenly distributed on the surface thereof and which points towards the susceptor. In order to prevent parasitic accumulation in the gas inlet organ, the gas outlet surface is formed by a gas-permeable diffuser plate (15), which can extend parallel to a gas outlet plate (13) having a plurality of gas outlet holes (14) arranged in the form of sieves.

IPC 1-7
C23C 16/455

IPC 8 full level
C23C 16/455 (2006.01); **H01L 21/205** (2006.01); **C23C 16/44** (2006.01)

CPC (source: EP KR)
C23C 16/455 (2013.01 - EP KR); **C23C 16/45568** (2013.01 - EP); **C23C 16/45572** (2013.01 - EP)

Citation (search report)
See references of WO 03078681A1

Designated contracting state (EPC)
AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LI LU MC NL PT RO SE SI SK TR

DOCDB simple family (publication)
WO 03078681 A1 20030925; AU 2003212349 A1 20030929; DE 10211442 A1 20030925; EP 1485518 A1 20041215; JP 2005520932 A 20050714; KR 20040101261 A 20041202; TW 200305658 A 20031101

DOCDB simple family (application)
EP 0302608 W 20030313; AU 2003212349 A 20030313; DE 10211442 A 20020315; EP 03708229 A 20030313; JP 2003576671 A 20030313; KR 20047013660 A 20030313; TW 92105594 A 20030314